

Electronic Patent Application Fee Transmittal

Application Number:	10805890
Filing Date:	22-Mar-2004
Title of Invention:	Method of plasma etching of high-K dielectric materials with high selectivity to underlying layers
First Named Inventor:	Padmapani C. Nallan
Filer:	Keith Patrick Taboada
Attorney Docket Number:	7017 C1/ETCH/METAL-NVM/JB

Filed as Large Entity

Utility Filing Fees

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
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Basic Filing:

Pages:

Claims:

Miscellaneous-Filing:

Petition:

Patent-Appeals-and-Interference:

Post-Allowance-and-Post-Issuance:

Statutory disclaimer	1814	1	130	130
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Extension-of-Time:

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Total in USD (\$)				130